

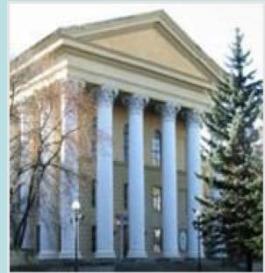
# ULTRAVIOLET ASTRONOMY IN THE XXI CENTURY

e-Workshop 2020 – October 27-29

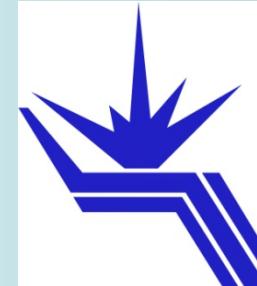
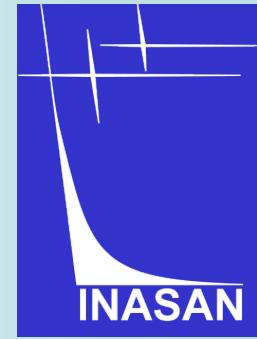
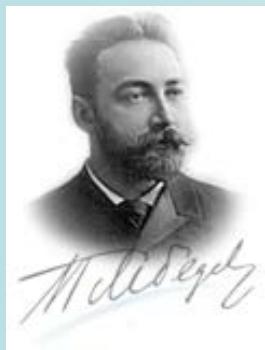


The Network for Ultraviolet Astronomy

# CCD and CMOS quantum efficiency evaluation in the EUV and VUV spectral ranges



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# Outline

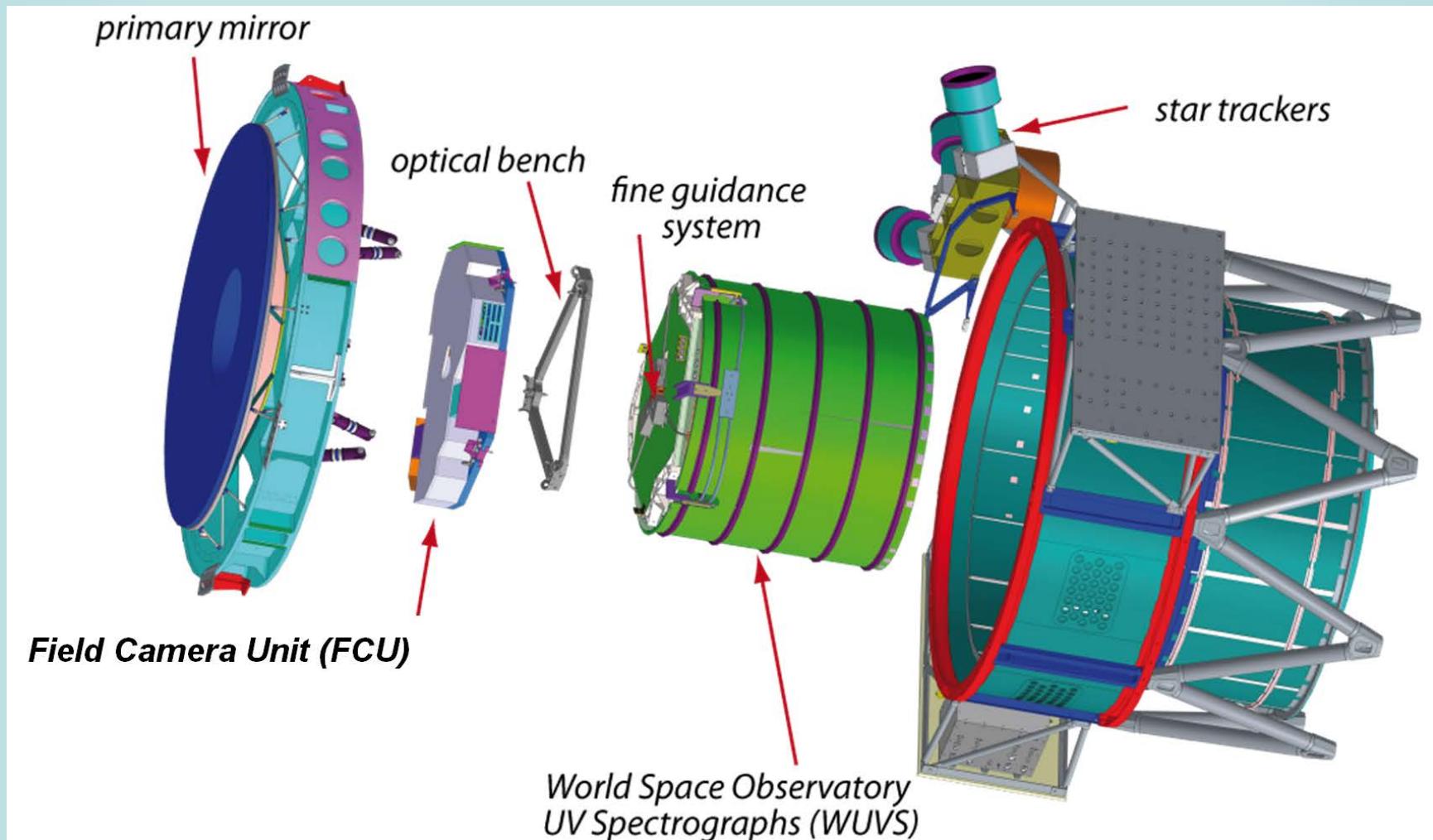
1. Introduction. WSO-UV spectrographs
2. Quantum efficiency (QE) evaluation procedures taken at „Kosmos“ metrological station (VEPP-4M, INP)
3. CCD and CMOS QE evaluation results in VUV and EUV spectral ranges

# **WSO-UV project objectives**

## **(World Space Observatory - UltraViolet)**

- Physics of the Early Universe
- Star-forming processes in galaxies
- Formation and evolution of galaxies
- Observation of supermassive stars
- Exploring forming processes of our Galaxy
- Observation of protoplanetary disks
- Investigations of exoplanets` atmospheres
- Observation of remote objects of Solar system

# WSO-UV Instrumental Facility Layout



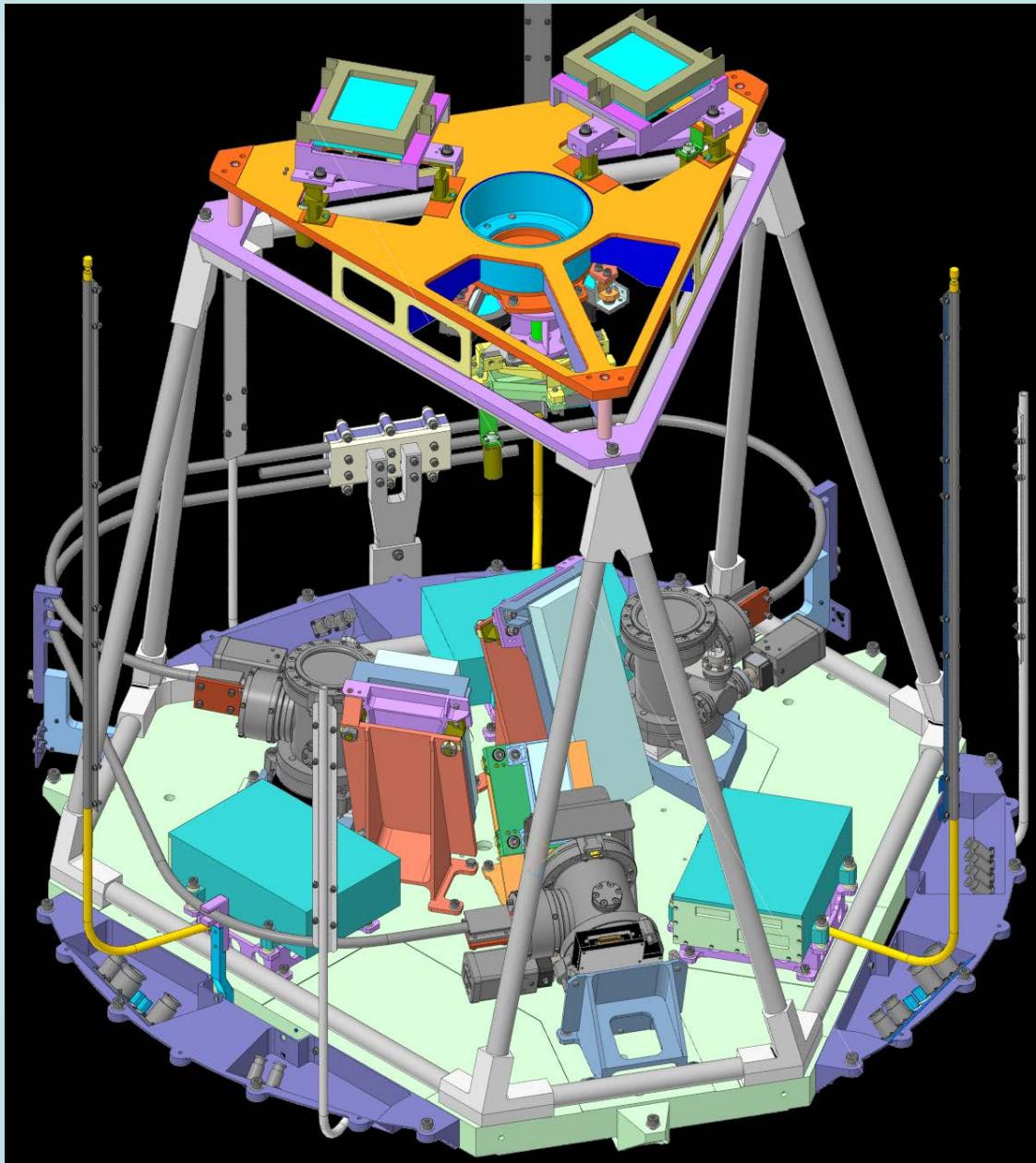
T-170M is 1.7 m Ritchey-Chretien telescope

# World Space Observatory UV Spectrographs (WUVS)

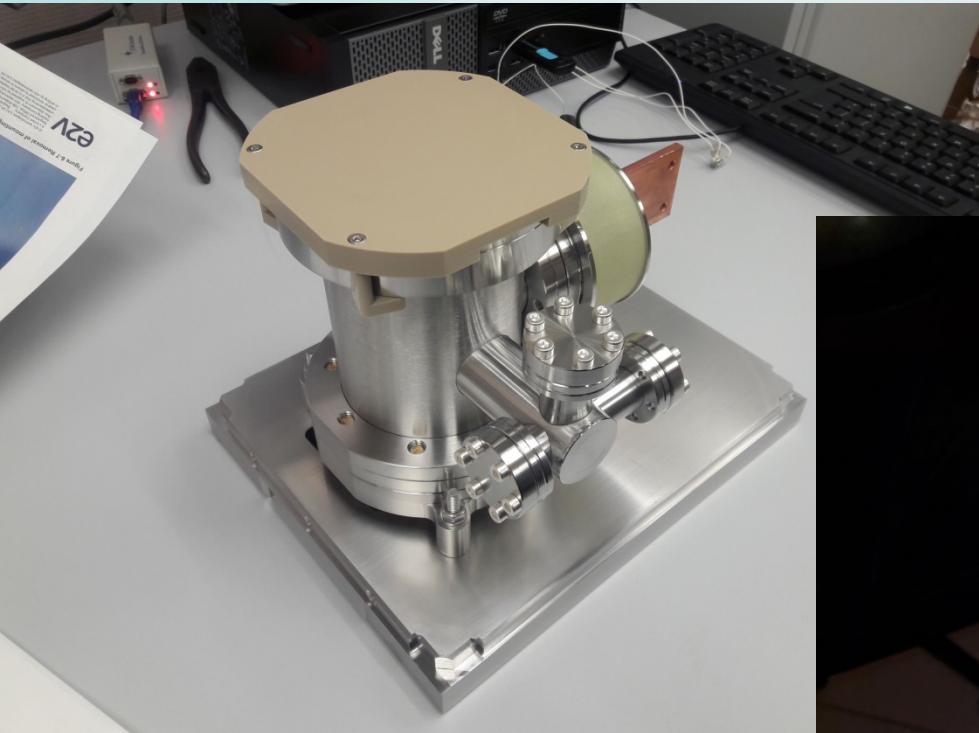
1. VUV echellé grating spectrometer (VUVES):  
Spectral range 115-176 nm, resolution  $\sim$ 50000
2. UV echellé grating spectrometer (UVES):  
Spectral range 174-310 nm, resolution  $\sim$ 50000
3. Long Slit Spectrograph (LSS):  
Spectral range 115-305 nm, resolution  $\sim$ 1000

\*B.Shustov *et al.*, *Astrophys. Space Sci.* **354**, 155 (2014).

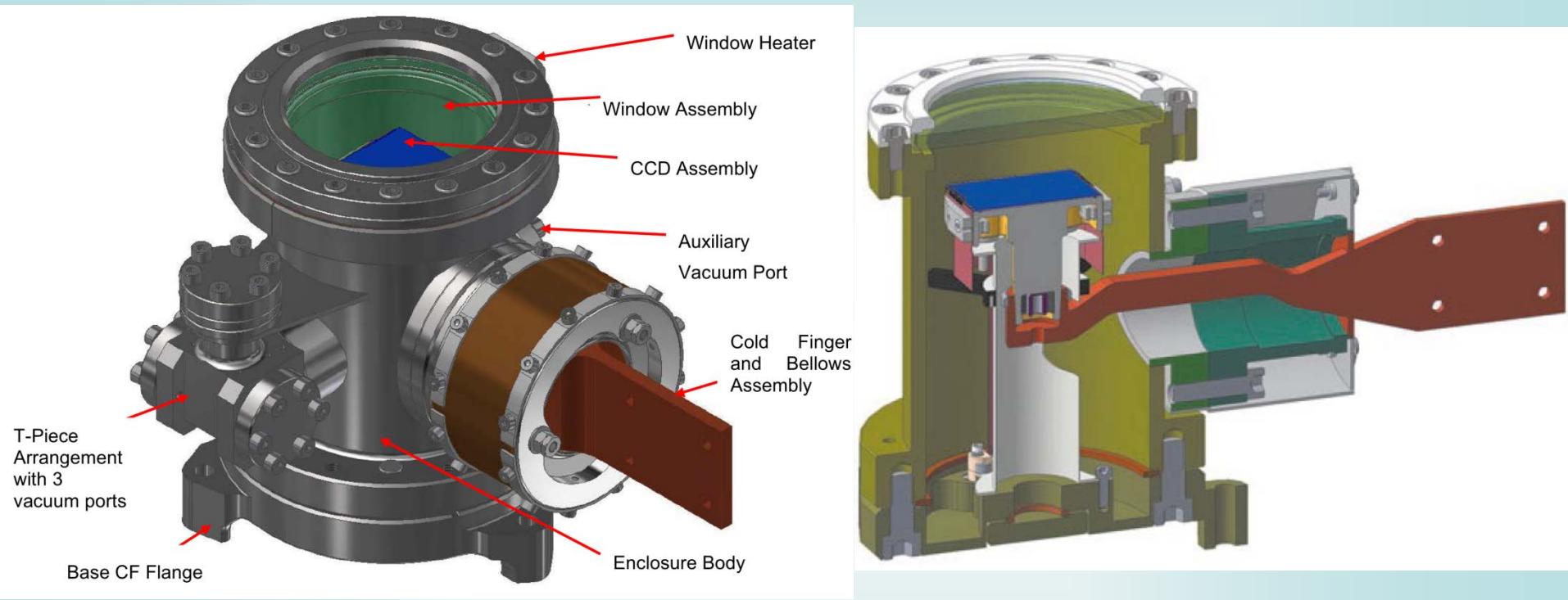
# WUVS optical unit with CCD detectors



# WUVS CCD detectors



# WUVS CCD detectors

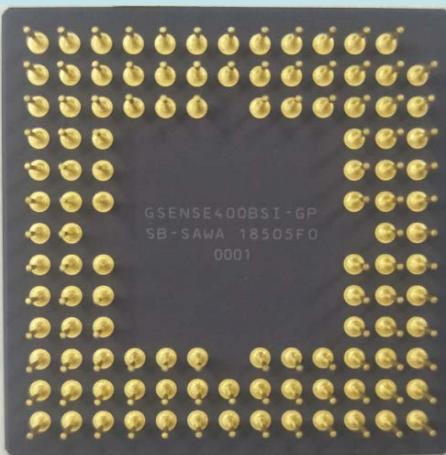
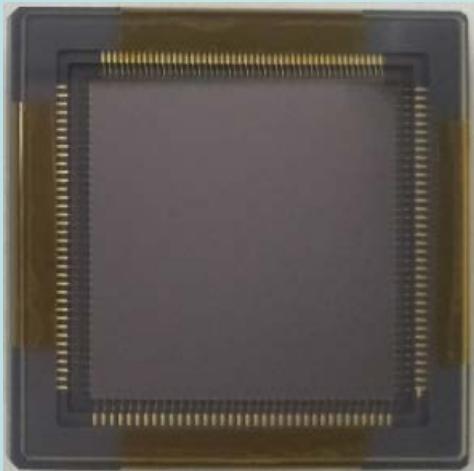


CCD format:  $4096 \times 3112$  pixels of  $12 \mu\text{m}$

Protective UV-transparent window material:  $\text{MgF}_2$

CCD operating temperature:  $-100^\circ\text{C}$

# CMOS sensors as alternative



*GPIXEL company (China) is able to produce various CMOS sensors sized up to 60x60mm. Back thinning process and back surface treatment were used to improve QE values in EUV and VUV spectral ranges.*

Stronger annealing

Weaker annealing

- G400BSI-GP LB-SA
- G400BSI-GP LB-WA
- G400BSI-GP LB-SAWA

Stronger annealing

Weaker annealing

- G400BSI-GP SB-SA
- G400BSI-GP SB-WA
- G400BSI-GP SB-SAWA

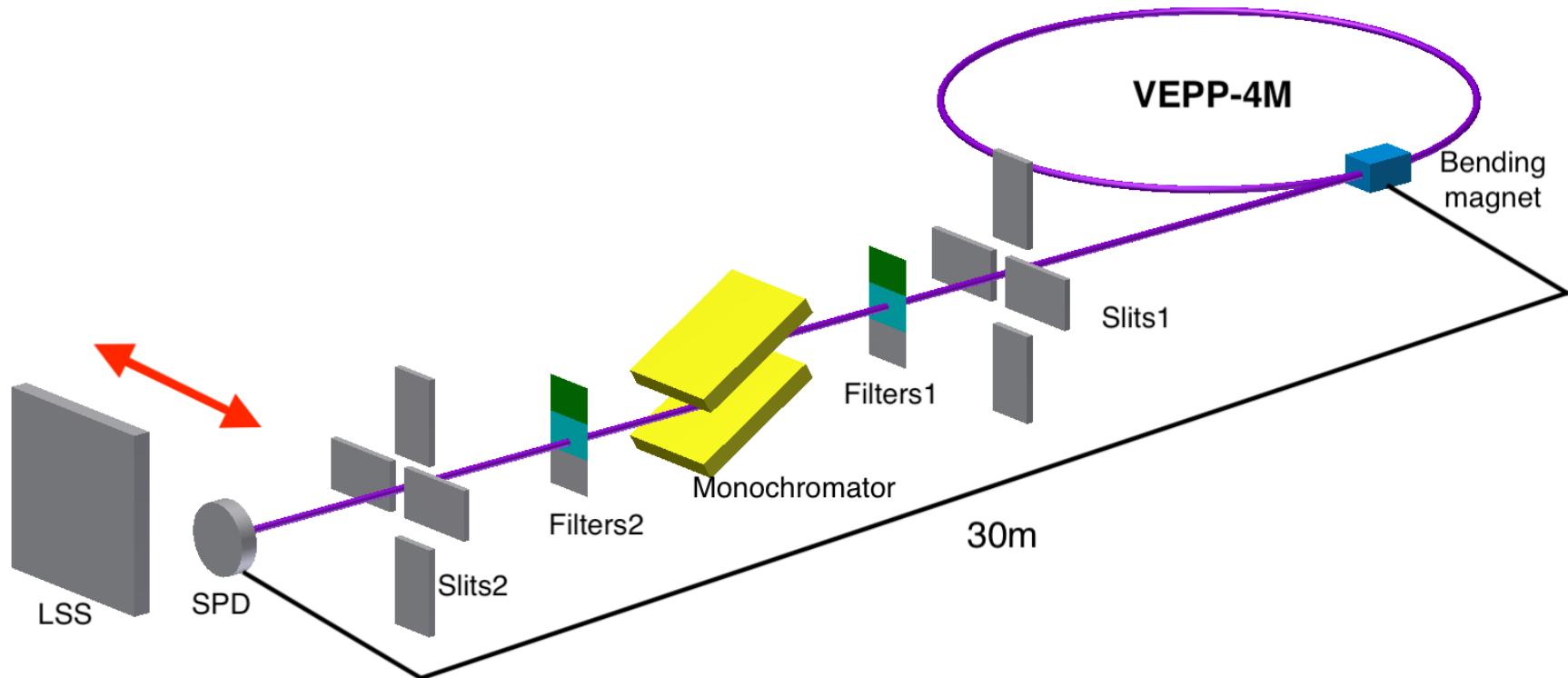
• (LB) Larger boron implantation dose

• (SB) Smaller boron implantation dose

## CMOS with different surface treatment were tested

# „Kosmos“ metrological station layout

beamline №10 at VEPP-4M synchrotron radiation source  
in Budker Institute of Nuclear Physics (INP), Novosibirsk

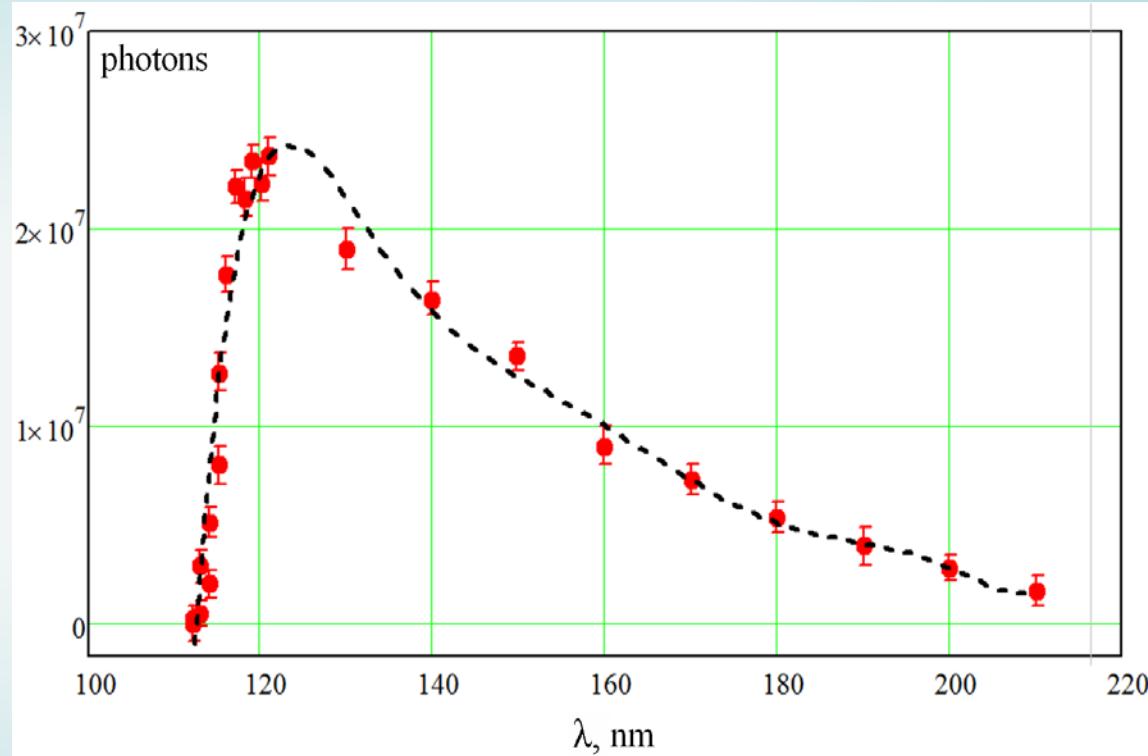


# Absolutely calibrated reference detector — SPD



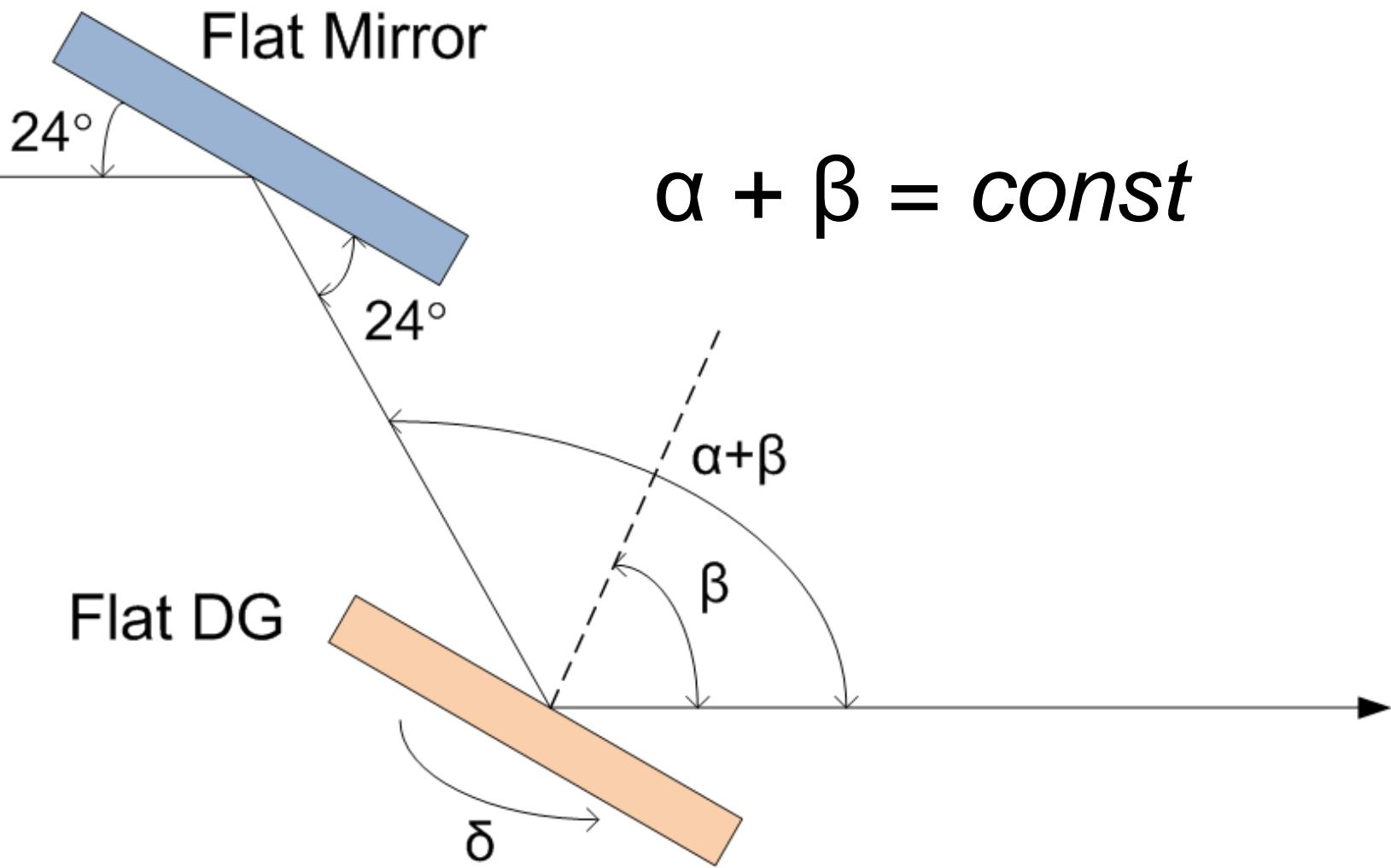
Sensitive surface  
 $1 \text{ cm}^2$

Calibrated at PTB  
2005, 2017

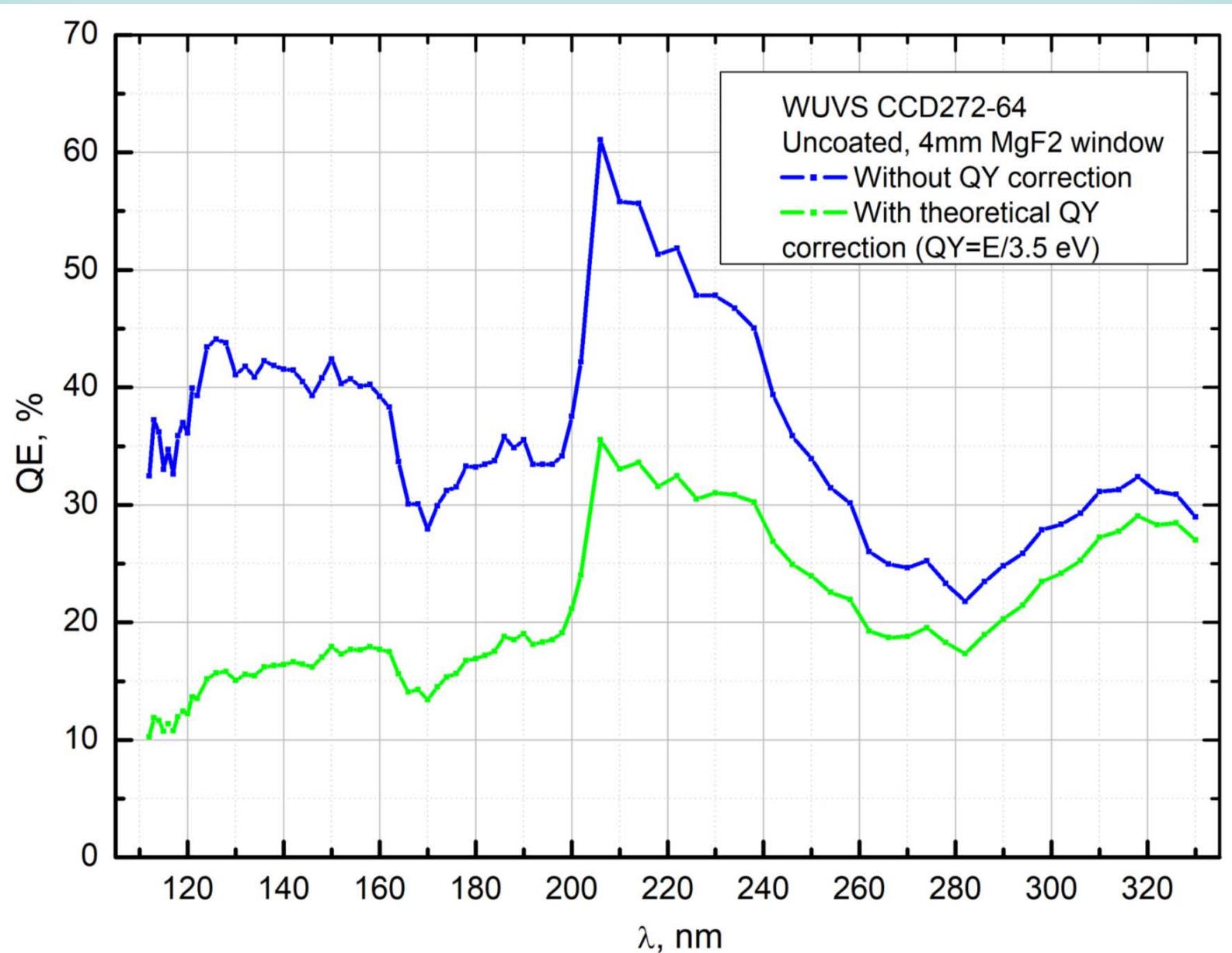


Photon flux at „Kosmos“ station  
in 110-220 nm spectral range  
(with  $\text{MgF}_2$  filter).

# „Kosmos“ diffraction grating (DG) EUV/VUV monochromator layout

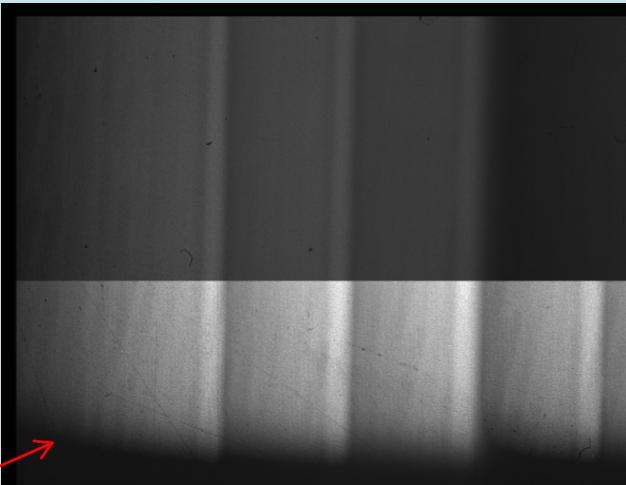


# Experimental Results for WUVS CCD

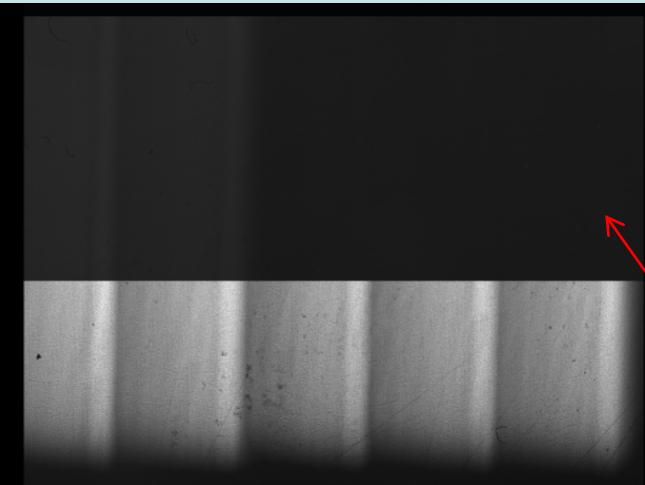


# Gradient anti-reflection coating

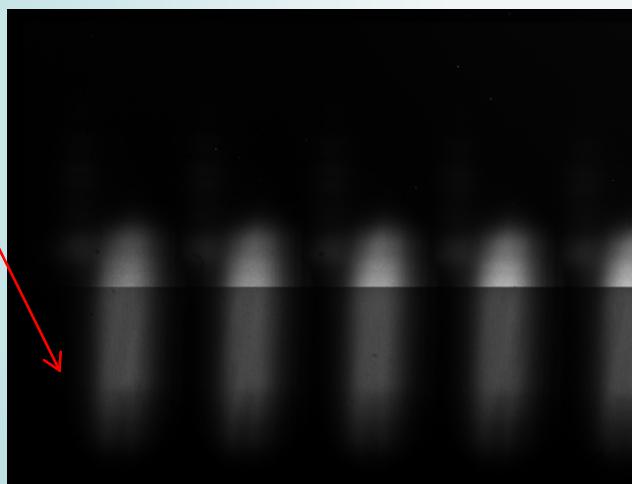
180 nm  
optimization



310 nm  
optimization

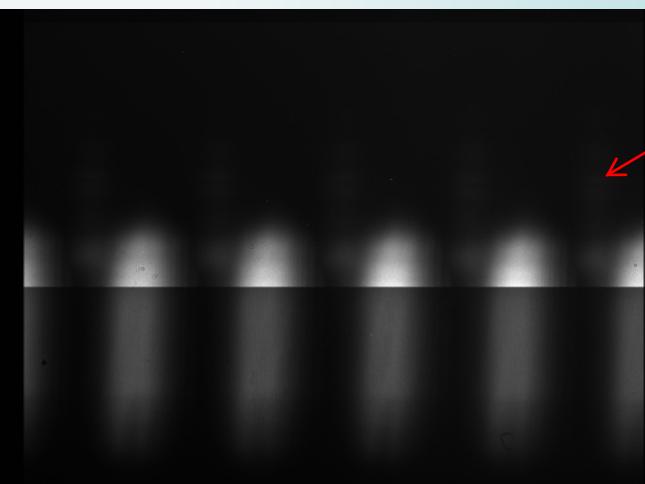


Uncoated



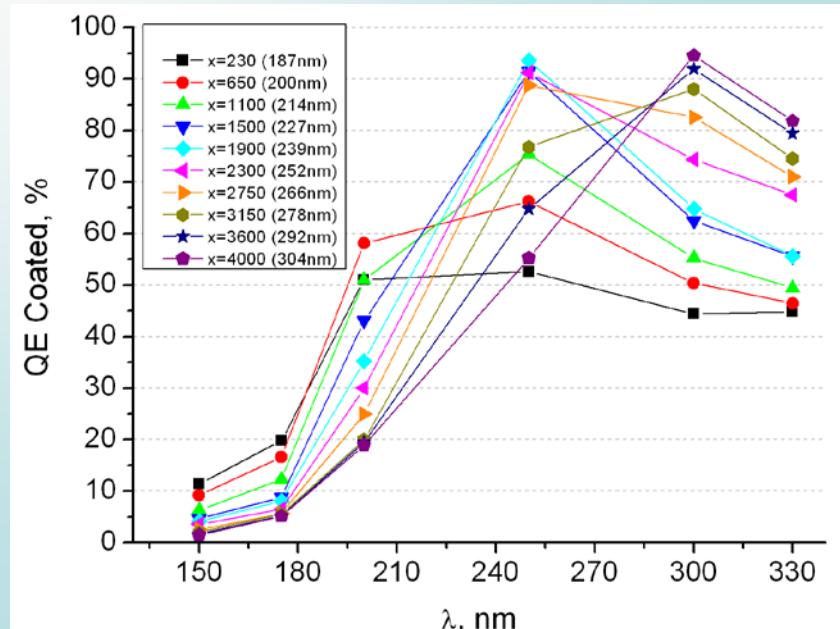
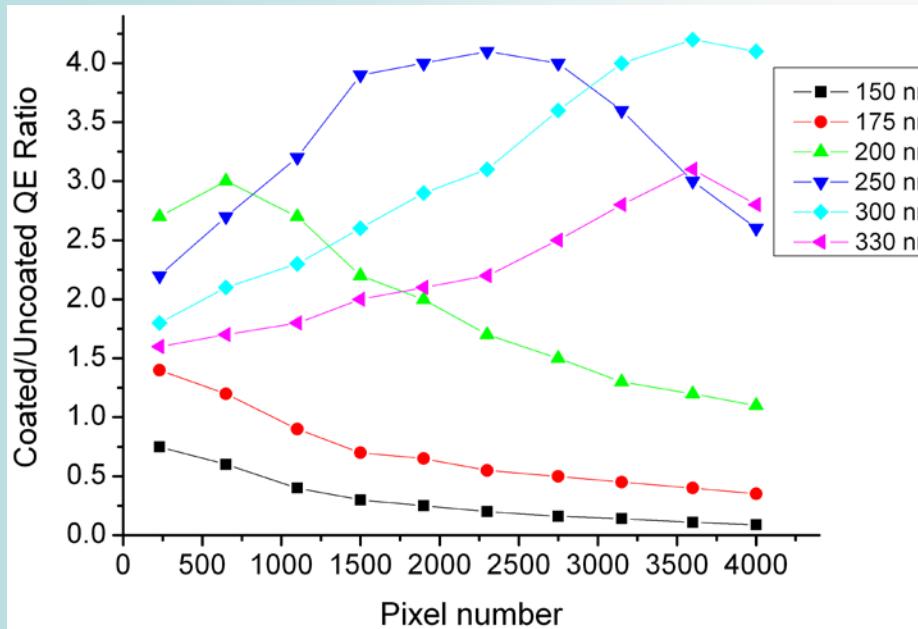
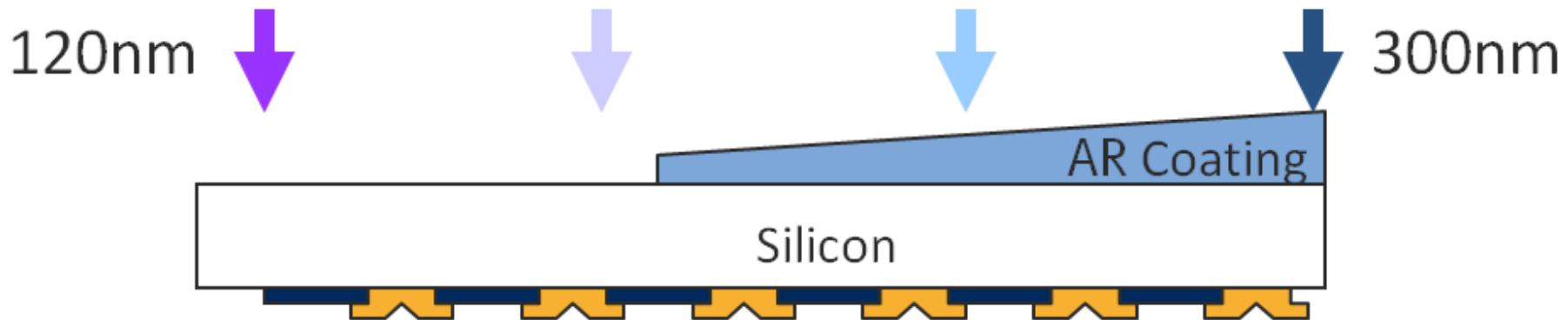
Illumination at 120 nm

Gradient  
AR  
coating

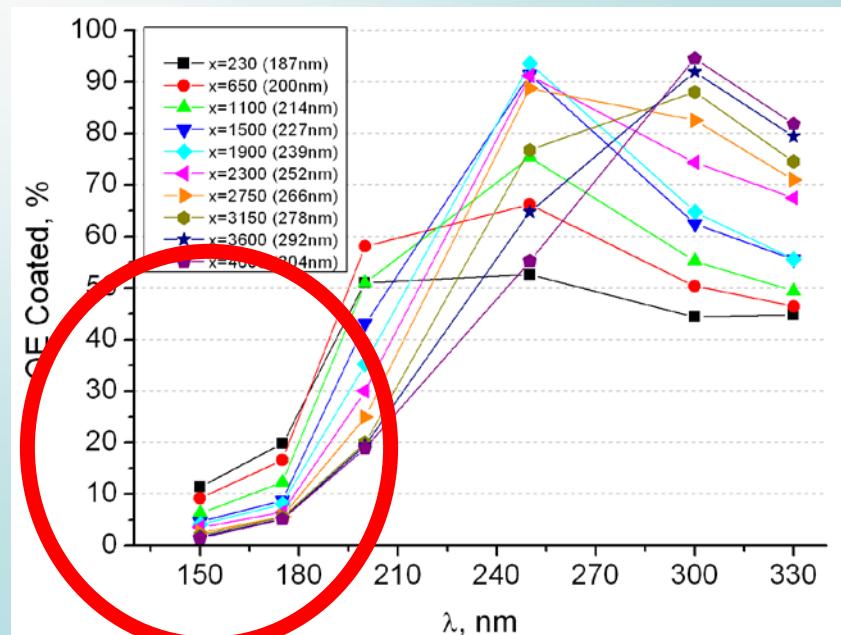
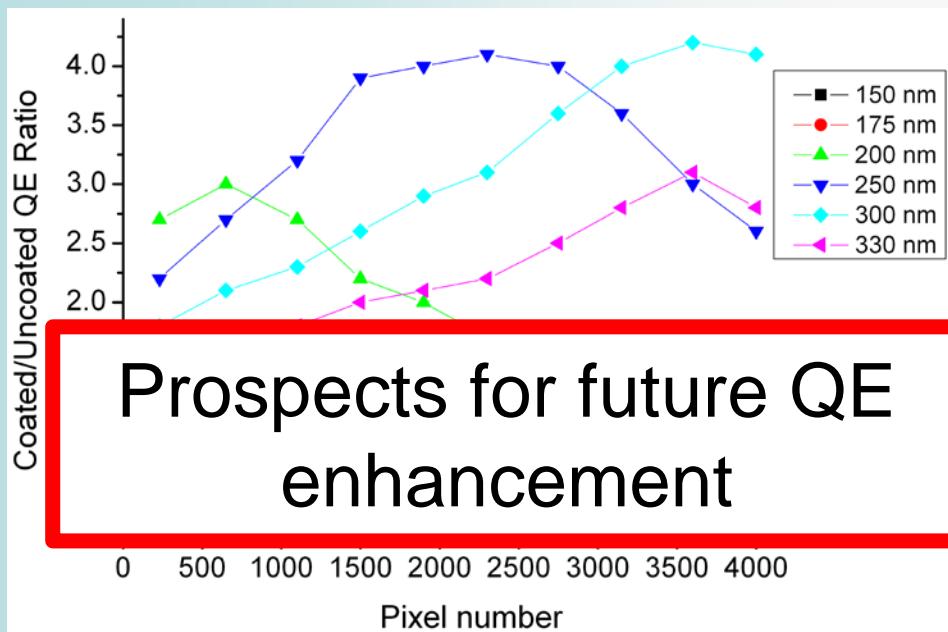
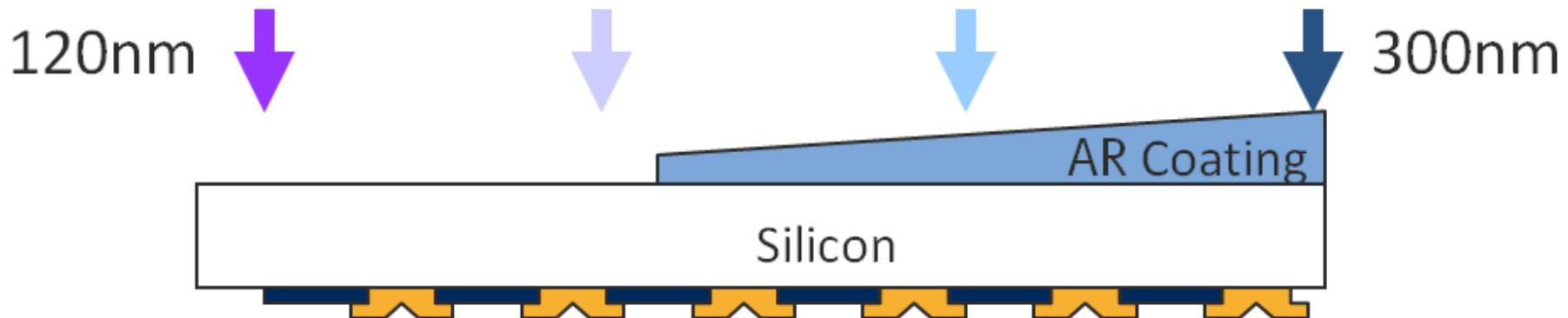


Illumination at 300 nm

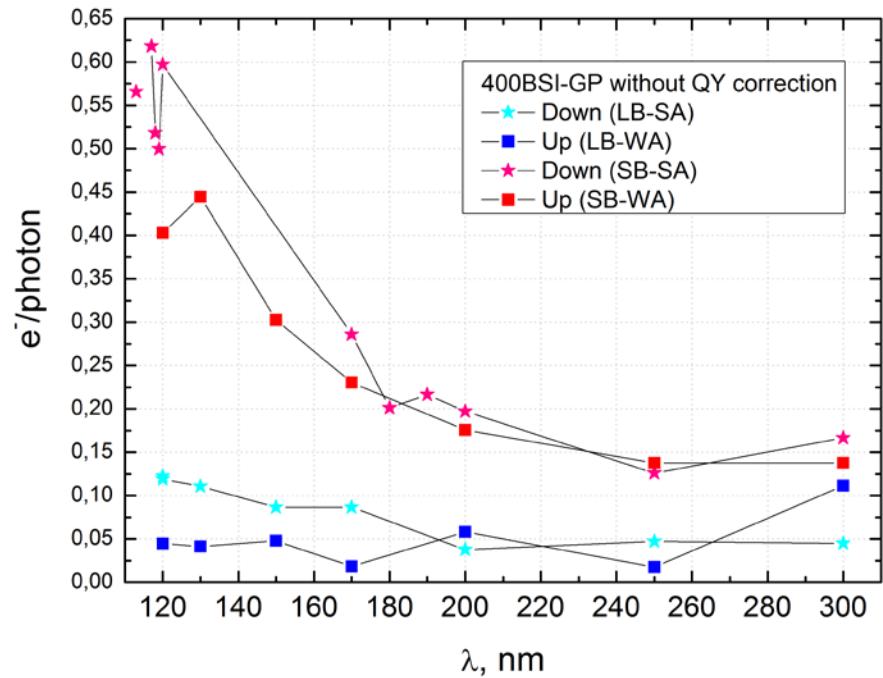
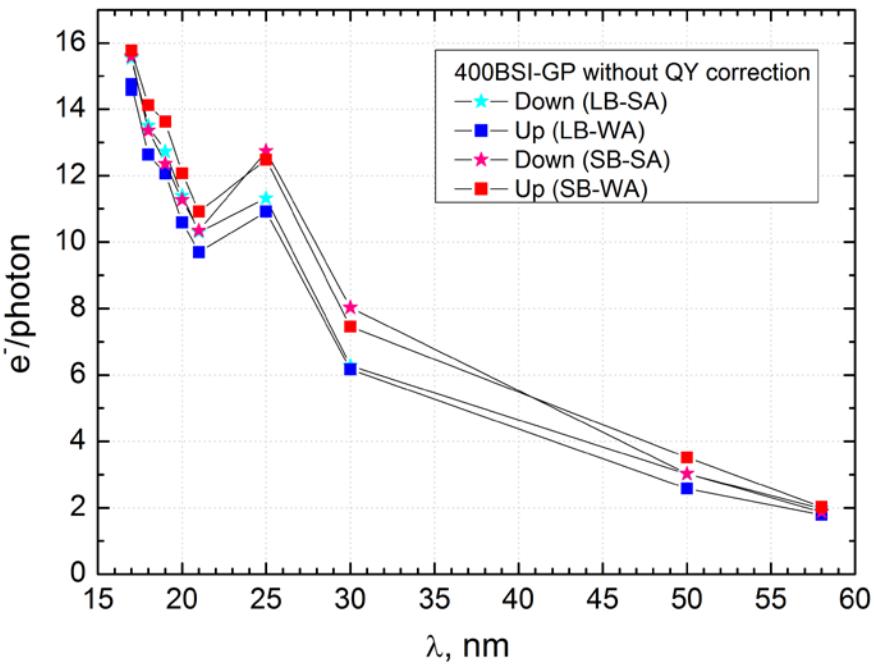
# Experimental Results for WUVS CCD with gradient anti-reflection coating



# Experimental Results for WUVS CCD with gradient anti-reflection coating



# CMOS Experimental Results



EUV

VUV

SB/LB — Strong/Low Boron implantation dose  
SA/WA — Strong/Weak Annealing

# Summary

- Quantum efficiency measurements of VUV CCD and CMOS detectors were conducted using synchrotron radiation from VEPP-4M
- CCD+MgF<sub>2</sub> QE values are ~15% in 112-200 nm range, and ~30% (after QY correction) in 210-330 nm range
- CMOS QE values are ~10% in 112-330 nm VUV range, and ~80% in 17-58 nm EUV range
- Boron implantation increases CMOS QE in EUV&VUV
- Usage of special anti-reflection coatings paves the way to increase CCD QE values up to 4x in 220-310 nm range
- Design of new AR coatings could increase CCD QE values at shorter wavelengths

# Acknowledgements

- We acknowledge VEPP-4M operating team for sustainable technical support and excellent synchrotron performance
- We acknowledge Teledyne e2v for the design and production of the CCD detectors for WSO-UV space project
- We express our gratitude to Gpixel company to provide the CMOS for QE evaluation